L Number	Hits	Search Text	DB	Time stamp
1	9	(("5308447") or ("4675530") or ("5475319") or ("6232134") or ("5474877") or ("5721090") or ("5587587") or ("6458704") or ("6162565")).PN.	USPAT; US-PGPUB	2003/12/30 09:30
2	2855	electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)	USPAT; US-PGPUB	2003/12/30 10:01
3	438	(electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) and wafer	USPAT; US-PGPUB	2003/12/30 09:31
4	131	((electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) and wafer) and solution	USPAT; US-PGPUB	2003/12/30 09:31
5	26	((electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) and wafer) and dispens$2	USPAT; US-PGPUB	2003/12/30 09:34
6	2711	electrostatic near2 chuck	USPAT; US-PGPUB	2003/12/30 09:41
7	154	(electrostatic near2 chuck) and dispens$2	USPAT; US-PGPUB	2003/12/30 09:38
8	3959	static near2 (sens$2 detect$3 monitor$2 regulat$3)	USPAT; US-PGPUB	2003/12/30 09:38
9	0	((electrostatic near2 chuck) and dispens$2) and (static near2 (sens$2 detect$3 monitor$2 regulat$3))	USPAT; US-PGPUB	2003/12/30 09:35
10	127	((electrostatic near2 chuck) and dispens$2) and (sens$2 detect$3 monitor$2 regulat$3)	USPAT; US-PGPUB	2003/12/30 09:35
11	7813	wafer near2 (sens$2 detect$3 monitor$2 regulat$3)	USPAT; US-PGPUB	2003/12/30 09:38
12	368	(wafer near2 (sens$2 detect$3 monitor$2 regulat$3)) and dispens$2	USPAT; US-PGPUB	2003/12/30 09:38
13	7	(electrostatic near2 chuck) and ((wafer near2 (sens$2 detect$3 monitor$2 regulat$3)) and dispens$2)	USPAT; US-PGPUB	2003/12/30 09:38
14	51	electrostatic and ((wafer near2 (sens$2 detect$3 monitor$2 regulat$3)) and dispens$2)	USPAT; US-PGPUB	2003/12/30 09:43
15	341	(electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) same (wafer substrate plasma)	USPAT; US-PGPUB	2003/12/30 09:43
16	65	(electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) near3 (wafer substrate plasma)	USPAT; US-PGPUB	2003/12/30 09:45
17	6933	dispens$2 near2 control$3	USPAT; US-PGPUB	2003/12/30 09:46
18	0	((electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) same (wafer substrate plasma)) and (dispens$2 near2 control$3)	USPAT; US-PGPUB	2003/12/30 09:46
19	1067	dispens$2 near2 controller	USPAT; US-PGPUB	2003/12/30 09:46
20	0	((electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) same (wafer substrate plasma)) and (dispens$2 near2 controller)	USPAT; US-PGPUB	2003/12/30 09:46
21	10	((electrostatic near2 (sens$2 detect$3 monitor$2 regulat$3)) same (wafer substrate plasma)) and dispens$2	USPAT; US-PGPUB	2003/12/30 09:49
22	21038	charge near2 (sens$2 detect$3 monitor$2 regulat$3)	USPAT; US-PGPUB	2003/12/30 09:49
23	1886	(charge near2 (sens$2 detect$3 monitor$2 regulat$3)) and wafer	USPAT; US-PGPUB	2003/12/30 10:01
24	135	((charge near2 (sens$2 detect$3 monitor$2 regulat$3)) and wafer) and dispens$2	USPAT; US-PGPUB	2003/12/30 10:01
25	2737	electrostatic near2 (sens$2 detect$3 monitor$2)	USPAT; US-PGPUB	2003/12/30 10:01
26	306	(electrostatic near2 (sens$2 detect$3 monitor$2)) same (wafer substrate)	USPAT; US-PGPUB	2003/12/30 10:13
27	10	((electrostatic near2 (sens$2 detect$3 monitor$2)) same (wafer substrate)) and dispens$2	USPAT; US-PGPUB	2003/12/30 10:01

28	3	("4564280" | "5487398" | "5555234").PN.	USPAT	2003/12/30 10:06
29	10	5854953.URPN.	USPAT	2003/12/30 10:07
30	5	("4396705" | "5762749" | "5854953" | "5887605" | "6334902").PN.	USPAT	2003/12/30 10:09
31	57	(electrostatic near2 (sens$2 detect$3 monitor$2)) near3 (wafer substrate)	USPAT; US-PGPUB	2003/12/30 10:15
32	4957	control$2 near2 dispensing	USPAT; US-PGPUB	2003/12/30 10:16
33	13	(electrostatic near2 (sens$2 detect$3 monitor$2)) and (control$2 near2 dispensing)	USPAT; US-PGPUB	2003/12/30 10:25
34	11952	reduc$2 near2 charge	USPAT; US-PGPUB	2003/12/30 10:33
35	5383	(reduc$2 near2 charge) and (wafer substrate)	USPAT; US-PGPUB	2003/12/30 10:45
36	5	(control$2 near2 dispensing) and ((reduc$2 near2 charge) and (wafer substrate))	USPAT; US-PGPUB	2003/12/30 10:26
37	10007	sens$3 near2 charge	USPAT; US-PGPUB	2003/12/30 10:47
38	952	(sens$3 near2 charge) same (wafer substrate workpiece)	USPAT; US-PGPUB	2003/12/30 10:34
39	38	((sens$3 near2 charge) same (wafer substrate workpiece)) and dispensing	USPAT; US-PGPUB	2003/12/30 10:44
40	27	((sens$3 near2 charge) same (wafer substrate workpiece)) and dispenser	USPAT; US-PGPUB	2003/12/30 10:38
41	532	dispensing near2 controller	USPAT; US-PGPUB	2003/12/30 10:45
42	115	(dispensing near2 controller) and (wafer substrate)	USPAT; US-PGPUB	2003/12/30 11:05
43	8	(sens$3 near2 charge) and ((dispensing near2 controller) and (wafer substrate))	USPAT; US-PGPUB	2003/12/30 10:48
44	25147	(detect$3 sens$3 measur$2) near2 charge	USPAT; US-PGPUB	2003/12/30 11:04
45	10007	(sens$3 near2 charge) and ((detect$3 sens$3 measur$2) near2 charge)	USPAT; US-PGPUB	2003/12/30 10:49
46	9	((dispensing near2 controller) and (wafer substrate)) and ((detect$3 sens$3 measur$2) near2 charge)	USPAT; US-PGPUB	2003/12/30 10:49
47	13	(dispensing near2 controller) and ((detect$3 sens$3 measur$2) near2 charge)	USPAT; US-PGPUB	2003/12/30 10:51
48	1088	photoresist and ((detect$3 sens$3 measur$2) near2 charge)	USPAT; US-PGPUB	2003/12/30 10:51
49	43	(photoresist and ((detect$3 sens$3 measur$2) near2 charge)) and dispenser	USPAT; US-PGPUB	2003/12/30 11:05
50	116516	(detect$3 sens$3 measur$2) near2 voltage	USPAT; US-PGPUB	2003/12/30 11:06
51	96	((detect$3 sens$3 measur$2) near2 voltage) near2 wafer	USPAT; US-PGPUB	2003/12/30 11:04
52	26955	((detect$3 sens$3 measur$2) near2 voltage) and (wafer substrate)	USPAT; US-PGPUB	2003/12/30 11:05
53	4613	((detect$3 sens$3 measur$2) near2 voltage) same (wafer substrate)	USPAT; US-PGPUB	2003/12/30 11:05
54	579	((detect$3 sens$3 measur$2) near2 voltage) near3 (wafer substrate)	USPAT; US-PGPUB	2003/12/30 11:06
55	6	(((detect$3 sens$3 measur$2) near2 voltage) near3 (wafer substrate)) and dispenser	USPAT; US-PGPUB	2003/12/30 11:06
56	12081	(detect$3 sens$3 measur$2) near2 ion	USPAT; US-PGPUB	2003/12/30 11:06
57	220	((detect$3 sens$3 measur$2) near2 ion) near3 (wafer substrate)	USPAT; US-PGPUB	2003/12/30 11:08
58	2	(((detect$3 sens$3 measur$2) near2 ion) near3 (wafer substrate)) and dispenser	USPAT; US-PGPUB	2003/12/30 11:09
59	8	("4312935" | "4610953" | "5019485" | "5144833" | "5178989" | "5701013" | "5702566" | "5858879").PN.	USPAT	2003/12/30 11:07
60	0	6479820.URPN.	USPAT	2003/12/30 11:08
61	3482	charge near2 accumulat$3 same (wafer substrate)	USPAT; US-PGPUB	2003/12/30 14:01
62	63	(charge near2 accumulat$3 same (wafer substrate)) and dispenser	USPAT; US-PGPUB	2003/12/30 11:16

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63	654	(charge near2 accumulat$3 same (wafer substrate)) and photoresist	USPAT; US-PGPUB	2003/12/30 12:36
64	8	((charge near2 accumulat$3 same (wafer substrate)) and photoresist) and dispenser	USPAT; US-PGPUB	2003/12/30 12:25
65	44	((charge near2 accumulat$3 same (wafer substrate)) and photoresist) and dispens$3	USPAT; US-PGPUB	2003/12/30 12:29
66	737	(charge near2 accumulat$3 same (wafer substrate)) and resist	USPAT; US-PGPUB	.2003/12/30 12:29
67	93	((charge near2 accumulat$3 same (wafer substrate)) and resist) and dispens$3	USPAT; US-PGPUB	2003/12/30 12:29
68	1	(charge near2 accumulat$3 same (wafer substrate)) and rinsing near2 liquid	USPAT; US-PGPUB	2003/12/30 12:38
69	61	(charge near2 accumulat$3 same (wafer substrate)) and rinsing	USPAT; US-PGPUB	2003/12/30 14:00
70	3	("4110810" | "4642728" | "5057966").PN.	USPAT	2003/12/30 12:42
71	0	6507474.URPN.	USPAT	2003/12/30 12:46
72	14	("4778536" | "4827371" | "5037506" | "5346586" | "5356478" | "5423944" | "5486267" | "5712198" | "5753137" | "5763016" | "5849639" | "5944907" | "5981960" | "6024887").PN.	USPAT	2003/12/30 12:49
73	11	("3652331" | "4104086" | "4149905" | "4409260" | "4526624" | "4668337" | "4894353" | "4901133" | "5108543" | "5459105" | "5531857").PN.	USPAT	2003/12/30 13:10
75	14	("3873209" | "3995216" | "4322979" | "4464627" | "4490618" | "4681451" | "4827212" | "4865453" | "5028132" | "5091691" | "5125740" | "5225690" | "5233291" | "5239183").PN.	USPAT	2003/12/30 13:35
76	7	("4083254" | "4322979" | "4681451" | "4891584" | "4941753" | "4992728" | "5065103").PN.	USPAT	2003/12/30 13:40
77	11	5233291.URPN.	USPAT	2003/12/30 13:43
78	8	("4498043" | "4769919" | "5036271" | "5140272" | "5225690" | "5233291" | "6037781" | "6075375").PN.	USPAT	2003/12/30 13:48
79	1	6150832.URPN.	USPAT	2003/12/30 13:50
80	9290	charge near2 (meter$2 measur$3)	USPAT; US-PGPUB	2003/12/30 14:00
81	217	(charge near2 (meter$2 measur$3)) and rinsing	USPAT; US-PGPUB	2003/12/30 14:00
82	124	((charge near2 (meter$2 measur$3)) and rinsing) and (wafer substrate)	USPAT; US-PGPUB	2003/12/30 14:07
83	437	361/226-228.ccls.	USPAT; US-PGPUB	2003/12/30 14:13
84	17	(charge near2 (meter$2 measur$3)) and 361/226-228.ccls.	USPAT; US-PGPUB	2003/12/30 14:14
85	1636	361/230-234.ccls.	USPAT; US-PGPUB	2003/12/30 14:14
86	36	(charge near2 (meter$2 measur$3)) and 361/230-234.ccls.	USPAT; US-PGPUB	2003/12/30 14:16